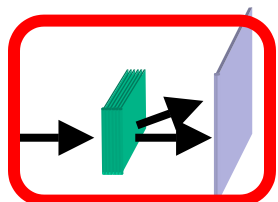
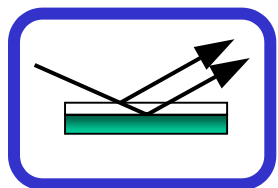
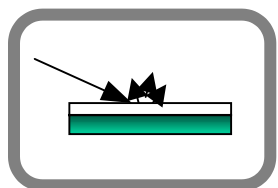


SANS Characterization of Nanoporous Thin Films for the Next Generation of Integrated Circuits



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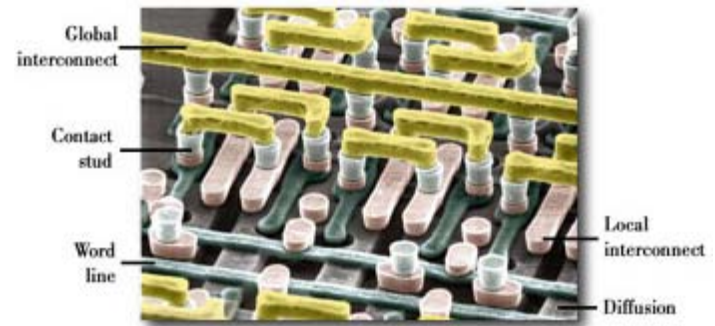
NIST
Polymers Division
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dielectric requirements for new integrated circuits

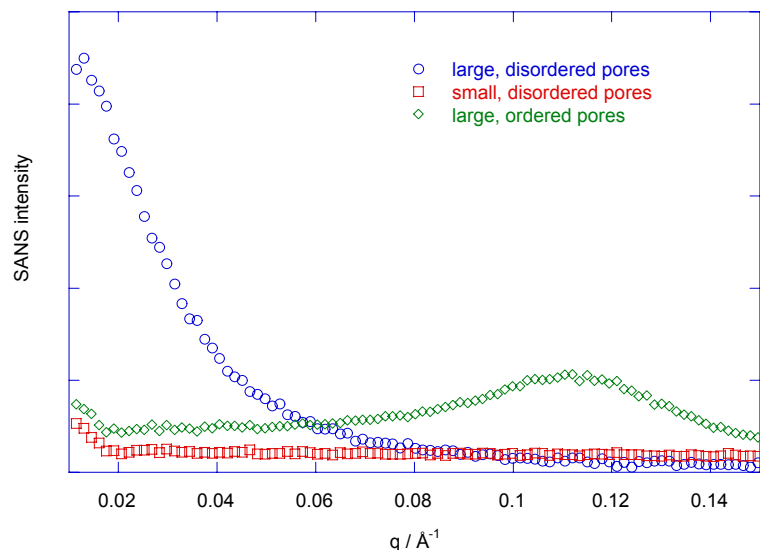
- the semiconductor industry is driven by miniaturization
 - low dielectric constant interlayer dielectrics are required
 - high switching speed
 - low crosstalk
 - the limits of conventional dielectric materials are being reached
 - $k = 2.7$ to 2.2 possible
 - lower values of dielectric constants (1.7 by 2007) require porosity
 - nano-porous dielectrics
 - pores can reduce k by reducing matrix volume fraction
 - other important physical properties are also changed
 - strength
 - barrier properties
- SANS characterization of morphology
 - pore volume fraction, P
 - matrix density, ρ
 - pore type and average size
 - pore connectivity
 - pore size distribution (PSD)



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SANS measurements of nano-porous films



- NCNR 8m SANS
- $0.01 \text{\AA}^{-1} < q < 0.15 \text{\AA}^{-1}$
- 6 h / sample
- 100 samples / 4 y

Note: all uncertainties are for one standard deviation. in cases where uncertainties are smaller than plot symbols, they are not shown.

- films are typically $1 \mu\text{m}$ thick on a 1 mm Silicon substrate
- high transmission of the substrate and high contrast of the film to pore required
- three morphology types
 - spin on film, porogen
 - large, disordered
 - chemical vapor deposition
 - small, disordered
 - surfactant templated
 - large, ordered

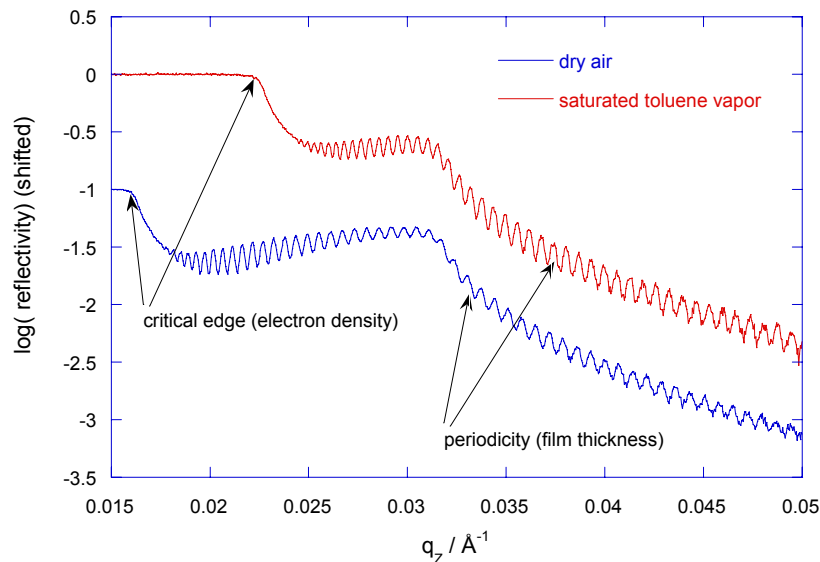
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SANS data analysis

- invariant analysis: $\int_0^{\infty} q^2 I(q) dq$ $P(1 - P)\sigma^2 \rho^2$
- Debye function, random: $I(q) = \frac{8\pi P(1 - P)\sigma^2 \rho^2 \xi^3}{(1 + q^2 \xi^2)^2}$
- Percus – Yevick spheres
 - monodisperse – radius, volume fraction
 - polydisperse - additional PSD type and width
 - ordering – non-overlap radius > pore size
- contrast match
 - absolute intensities not required
 - open pores & uniform matrix – wall density
 - closed pores – closed pore volume fraction and PSD

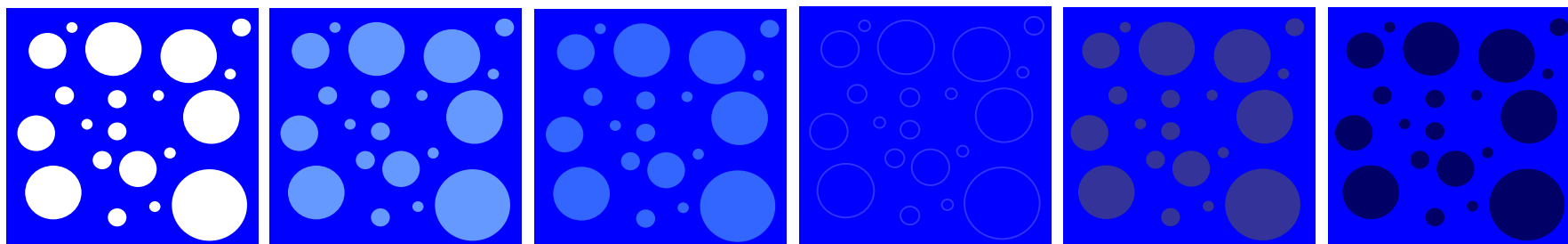
information from x-ray reflectivity (XR) and ion scattering



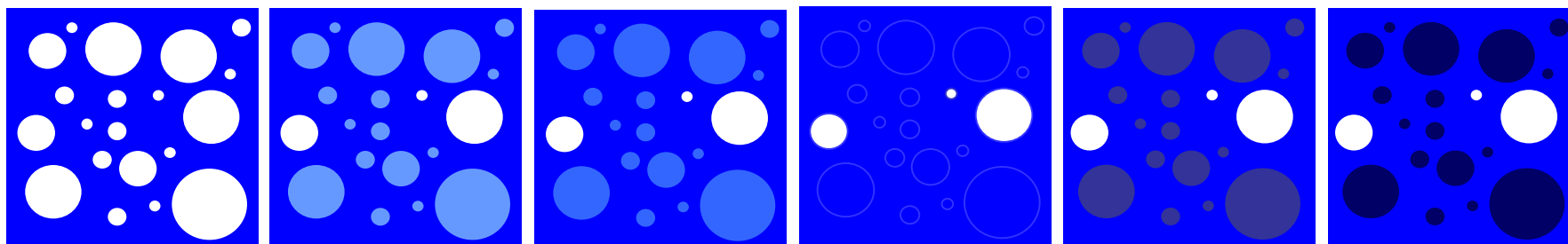
- routinely measured quantities
 - pore volume fraction
 - pore type and average size
 - matrix density
- techniques used
 - SANS, XR, ion scattering

- ion scattering (Rutherford back-scattering and forward recoil elastic scattering)
 - *in situ* measurements
 - atomic (H, C, O, Si) content for neutron and x-ray contrast
- x-ray reflectivity
 - 1 μm film thickness to ± 1 nm
 - electron density gives average mass density, ρ_{AVE}
 - Average mass density is a combination of pore volume fraction, P , and matrix density, ρ
 - $\rho_{\text{AVE}} = (1-P)\rho$

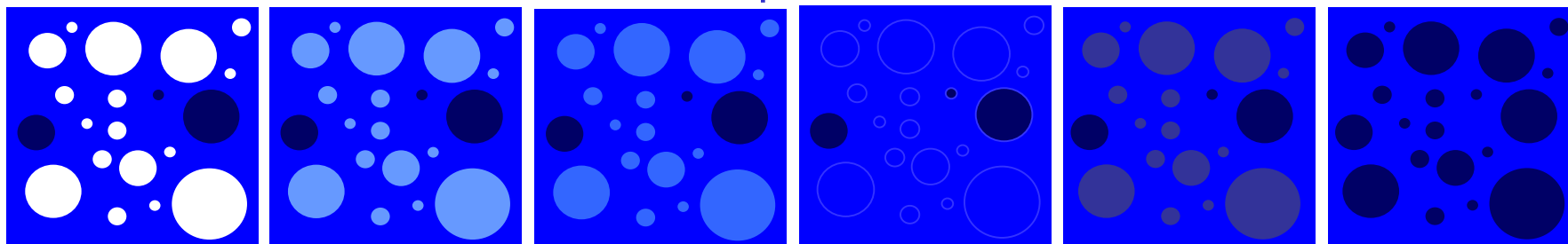
SANS contrast match – possible morphologies



No closed pores, uniform wall



Some closed pores, uniform wall



No closed pores, 2 phase wall

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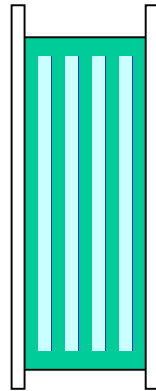
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SANS measurements using probe molecules

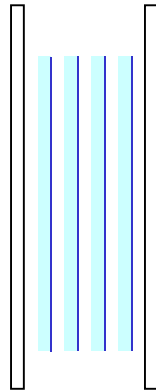
- SANS contrast match
 - fill pores with mixtures of proton and deuterium solvents
 - not dependent on morphology type
 - closed pore porosity measured directly
 - matrix swelling monitored by XR thickness
- SANS porosimetry
 - fill pores with match mixture at controlled vapor pressure
 - pores are filled by capillary action
 - pores are filled according to the Kelvin equation
 - $r = -2\gamma V / (RT) / \ln(P/P_0)$
 - SANS from unfilled pores – pore size distribution



SANS contrast match – vapor adsorption



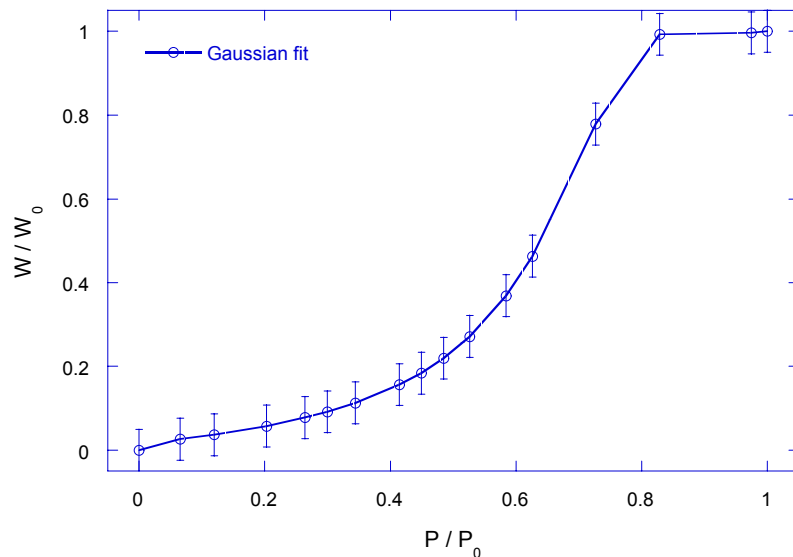
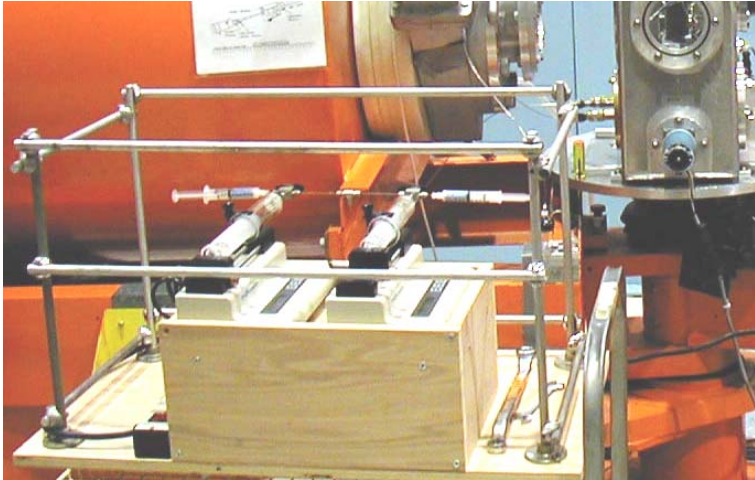
filled
cell



saturated
film

- film thickness is hundreds of times less than space between substrates
- a solvent filled SANS cell produces a large incoherent background
- use a saturated solvent vapor to fill the pores by capillary action
- incoherent scattering background is reduced to acceptable level
- a vacuum tight flow-through cell constructed

SANS contrast match – vapor adsorption

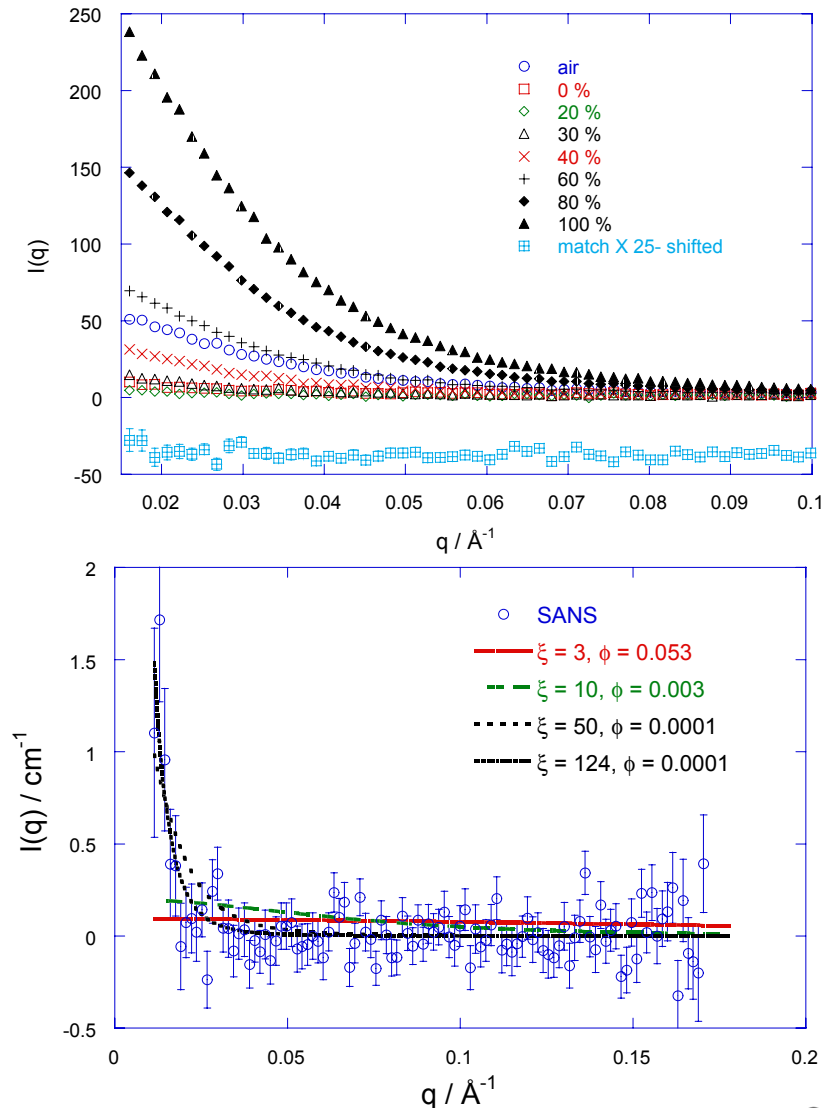


- syringe pumps deliver mixtures of saturated toluene- h_8 and toluene- d_8
- equilibrium is reached in < 30 min
- match point can be calculated from $I(q) \propto (\sigma\rho - (\sigma\rho)_{MATCH})^2$
- next, syringe pumps deliver mixtures of saturated match mixture and dry air
- pressures less than saturation fill pores described by Kelvin equation
- $r = - 2\gamma V / (RT) / \ln(P/P_0)$

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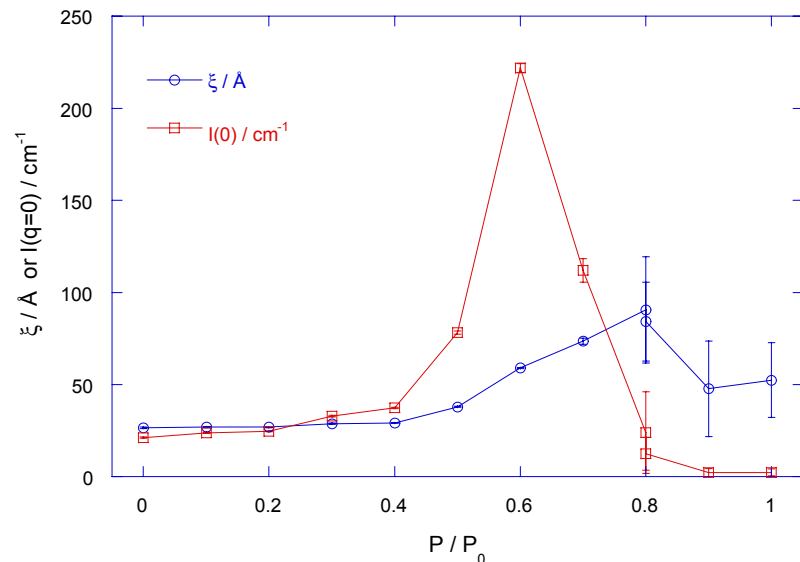
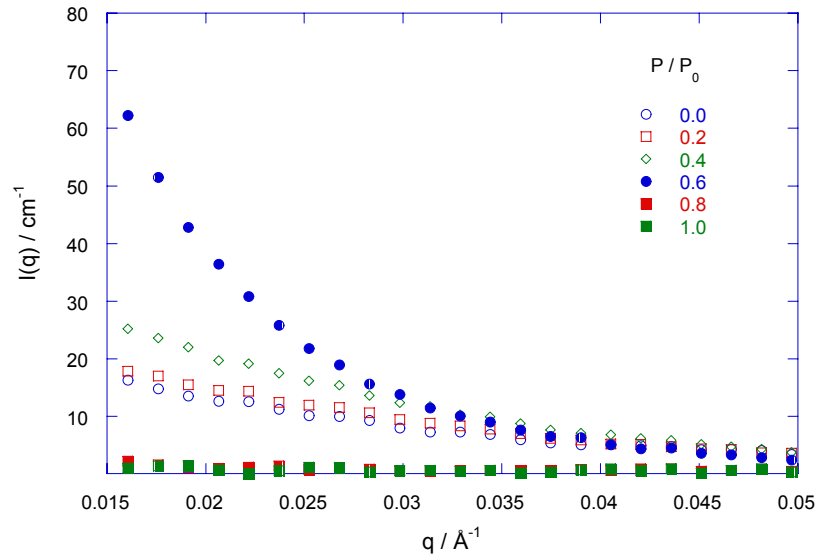
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SANS contrast match – xerogel



- SANS measurements are made pores filled with toluene- h_8 and $-d_8$
- total scattering goes through a minimum
- there is negligible scattering at the match point
- maximum closed pore porosity can be determined
- the match point is used to calculate wall density and porosity

SANS porosimetry – xerogel



- once match point has been determined, a mixture is prepared
- one syringe has saturated match mixture, the other has dry air
- various partial pressures are applied
- scattering comes from unfilled pores only
- SANS sizes can be compared to XR porosimetry values

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summary

- SANS can be used to measure 1 μm thick nanoporous films *in situ* on 1 mm Silicon substrate.
- various models can be applied to extract morphological information on technologically important films.
 - porosity, wall density, pore type and size
- contrast match can provide additional information
 - wall density without absolute intensities for any pore type
 - close pore porosity measured directly
- SANS porosimetry probes PSD



acknowledgements

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